(A1) a resin which contains a repeating unit represented by the following general formula (I), a repeating unit represented by the following general formula (NII) and a repeating unit having a group represented by any of the following general formulae (I-1) to (I-4), and whose dissolving rate toward an alkaline developing solution is increased by the action of an acid, and



(B) a compound which generates an acid upon irradiation with an actinic ray or a radiation,

$$R_{n1} = R_{n2} R_{n4}$$
 (I)

$$\begin{array}{c}
 + CH_2 - C + \\
 + COO - W
\end{array}$$
(NII)

 R_1 R_2 R_3 R_4 R_5 R_1 R_2 R_5 R_1 R_2 R_3 R_4 R_5 R_4 R_5 R_5 R_1 R_2 R_5 R_4 R_5 R_7 R_8 R_9 R_9

wherein in the formula (I), Rn₁ to Rn₄ each represents a hydrogen atom or an alkyl group which may have one or more substituents; and a is 0 or 1;

in the formula (NII), Rn₅ represents a hydrogen atom or a methyl group; A represents one group or a combination of two or more groups each selected from the group consisting of a single bond, an alkylene group, a cycloalkylene group, an ether group, a thioether group, a carbonyl group and an ester group; W represents a group represented by -C(Rna)(Rnb)(Rnc) or a group represented by -CH(Rnd)-O-Rne, wherein Rna, Rnb, and Rnc each represents a linear or branched

alkyl group having 1 to 20 carbon atoms or an alicyclic hydrocarbon group which may have a halogen atom, an alkyl group, an alkoxy group, an alkoxycarbonyl group, an acyl group or an acyloxy group as a substituent, provided that Rna and Rnb may be bonded to each other to form an alicyclic ring together with the carbon atom to which the groups are commonly attached and, in this case, Rnc is an alkyl group having 1 to 4 carbon atoms; Rnd represents a hydrogen atom or an alkyl group; Rne represents a linear or branched alkyl group having 1 to 20 carbon atoms or an alicyclic hydrocarbon group which may have a halogen atom, an alkyl group, an alkoxy group, an alkoxycarbonyl group, an acyl group or an acyloxy group as a substituent;

in the general formulae (I-1) to (I-4), R_1 to R_5 each independently represents a hydrogen atom, or an alkyl group, a cycloalkyl group or an alkenyl group which may have one or more substituents, and two of R_1 to R_5 may be bonded to each other to form a ring.

 \mathcal{N}

12 (amended). The positive photoresist composition according to claim 1, wherein the content of the resin (A) is from 40 to 99.9% by weight relative to the total solid content in the photogesist composition.



18 (amended). The positive photoresist composition according to claim 7, wherein the content of the resin (A2) is from 40 to 99.9% by weight relative to the total solid content in the photoresist composition.

Please add the following new claims:

19 (new). The positive photoresist composition according to claim 4, wherein the repeating unit having a group represented by any of general formulae (I-1) to (I-4) is of general formulae (I-1).

20 (new). The positive photoresist composition according to claim 4, wherein the repeating unit having a group represented by any of general formulae (I-1) to (I-4) is of general formulae (I-2).

21 (new). The positive photoresist composition according to claim 4, wherein the repeating unit having a group represented by any of general formulae (I-1) to (I-4) is of general formulae (I-3).

22 (new). The positive photoresist composition according to claim 4, wherein the repeating unit having a group represented by any of general formulae (I-1) to (I-4) is of general formulae (I-4).